

REMARKS

In the Office Action the Examiner noted that claims 1-15 are pending in the application, and the Examiner rejected all claims. By this Amendment, claims 1, 3, 9, and 11 have been amended. No new matter has been added. The Examiner's rejections are traversed below, and reconsideration of all rejected and objected to claims is respectfully requested.

Claim Rejections Under 35 USC §102

In item 1 on page 2 of the Office Action the Examiner rejected claims 1-2 and 9-10 under 35 U.S.C. §102(b) as being anticipated by U.S. Patent Application Publication No. 2002/0021089, issued to Kim (hereinafter referred to as "Kim"). The Applicants respectfully traverse the rejections by the Examiner.

Claim 1 of the present application, as amended, recites:

A method of manufacturing an electroluminescent display (EL) device, the method comprising:  
forming a first electrode unit arranged in a first predetermined pattern on a substrate;  
simultaneously forming two or more insulating layers, using a patterned single mask, covering the substrate and at least portions of the first electrode unit and defining a light emitting area having a second predetermined pattern, the insulating layers having different heights and patterns;  
forming an electroluminescent (EL) layer on the light-emitting area;  
forming a second electrode unit in a third predetermined pattern on the light emitting area; and  
sealing the substrate.

Therefore, the two or more insulating layers having different heights and patterns are simultaneously formed using a patterned single mask.

The Examiner states that Kim discloses a method of manufacturing an organic EL device using first and second masks to form an insulating layer and partition walls, including the step of "forming an insulating layer and partition walls having different thicknesses and patterns by simultaneously exposing through the first and second masks." This is in contrast to the method of manufacturing an EL device recited in claim 1 of the present application, in which a patterned single mask is used to simultaneously form two or more insulating layers. In Kim, the more complicated process requires two masks, as well as light exposure from opposite directions.

Therefore, Kim does not disclose the feature of "simultaneously forming two or more insulating layers, using a patterned single mask, covering the substrate and at least portions of the first electrode unit and defining a light emitting area having a second predetermined pattern, the insulating layers having different heights and patterns." Accordingly, Kim does not disclose every element of the Applicants' claim 1. In order for a reference to anticipate a claim, the reference must teach each and every element of the claim (MPEP §2131). Therefore, since Kim does not disclose the features recited in independent claim 1, as stated above, it is respectfully submitted that claim 1 patentably distinguishes over Kim, and withdrawal of the §102(b) rejection is earnestly and respectfully solicited.

Claim 2 depends from claim 1 and includes all of the features of that claim plus additional features which are not taught or suggested by Kim. Therefore, it is respectfully submitted that claim 2 also patentably distinguishes over Kim.

Claim 9 of the present application, as amended, recites "simultaneously forming inter-insulators, covering the substrate and at least portions of the first electrode unit and defining a light emitting area having a second predetermined pattern, and insulating walls, having a third predetermined pattern formed on at least portions of the inter-insulators, wherein the inter-insulators and the insulating walls have different heights and are formed using a patterned single mask." Therefore, for at least the reason that Kim discloses using two masks to form an insulating layer and partition walls having different thicknesses and patterns, claim 9 also patentably distinguishes over Kim.

Claim 10 depends from claim 9 and includes all of the features of that claim plus additional features which are not taught or suggested by Kim. Therefore, it is respectfully submitted that claim 10 also patentably distinguishes over Kim.

In item 2 on pages 2-3 of the Office Action the Examiner rejected claims 1-15 under 35 U.S.C. §102(e) as being anticipated by U.S. Patent Application Publication No. 2003/0052596, issued to Yi et al. (hereinafter referred to as "Yi"). The Applicants respectfully traverse these rejections by the Examiner.

The Examiner states that Yi discloses a method of fabricating an organic EL display comprising the step of "stacking an insulating layer pattern on a first area crossing with the first electrodes and a second area in parallel with the first electrodes wherein a half tone pattern is formed on the second area." However, while relying on this information to form the §102

rejection of claims 1-15, this step cited by the Examiner does not disclose the method recited in claims 1-15 of the present application. To wit, independent claim 1 recites forming two or more insulating layers covering "at least portions of the first electrode unit...., the insulating layers having different heights and patterns." This is in direct contrast to the EL display disclosed in Yi, in which the two layers having different heights do not each cover at least portions of the first electrode unit.

Figure 9B of Yi shows that the second area 44 of the insulating layer pattern cited by the Examiner, which is of a lower height than the first area 43 of the insulating layer pattern, is located between the first electrodes 42, and therefore does not cover "at least portions of the first electrode unit." This is supported by the Examiner's description of Yi, in which he contrasts the second area 44, being in parallel with the first electrodes 42, with the first area 43, which is crossing the first electrodes 42. Support for this assertion is also found throughout the disclosure of Yi. At least Figure 11B shows that the second area 44 of the insulating layer is formed at the same height as the first electrodes 42, and therefore could not cover any portion of the first electrodes 42. Further, paragraph [0082] of Yi states that the second area 44 of the insulating layer is formed "so as to lie between a plurality of the first electrodes 42," and therefore does not disclose forming the second area 44 of the insulating layer to cover any portion of the first electrodes 42. Therefore, since Yi does not disclose the features recited in independent claim 1, as stated above, it is respectfully submitted that for at least this reason claim 1 patentably distinguishes over Yi, and withdrawal of the §102(e) rejection is earnestly and respectfully solicited.

Claims 2-8 depend from claim 1 and include all of the features of that claim plus additional features which are not taught or suggested by Yi. Therefore, it is respectfully submitted that claims 2-8 also patentably distinguish over Yi.

Similarly, claim 9 of the present application recites "simultaneously forming inter-insulators, covering the substrate and at least portions of the first electrode unit and defining a light emitting area having a second predetermined pattern, and insulating walls, having a third predetermined pattern formed on at least portions of the inter-insulators, wherein the inter-insulators and the insulating walls have different heights and are formed using a patterned single mask." As the insulating walls are formed on at least portions of the inter-insulators, the inter-insulators have the lower height between the inter-insulators and the insulating walls. And, as recited in claim 9, the inter-insulators cover "at least portions of the first electrode unit," which is

in direct contrast to the disclosure of Yi. Therefore, at least for similar reasons as applied to the argument above that claim 1 patentably distinguishes over Yi, claim 9 also patentably distinguishes over Yi.

Claims 10-15 depend from claim 9 and include all of the features of that claim plus additional features which are not taught or suggested by Yi. Therefore, it is respectfully submitted that claims 10-15 also patentably distinguish over Yi.

Summary

In accordance with the foregoing, claims 1, 3, 9, and 11 have been amended. No new matter has been presented. Claims 1-15 are pending and under consideration.

There being no further outstanding objections or rejections, it is respectfully submitted that the application is in condition for allowance. An early action to that effect is courteously solicited.

Finally, if there are any formal matters remaining after this response, the Examiner is requested to telephone the undersigned to attend to these matters.

If there are any additional fees associated with filing of this Amendment, please charge the same to our Deposit Account No. 503333.

Respectfully submitted,

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